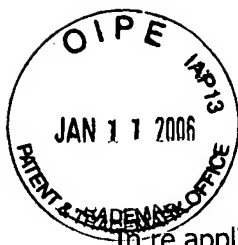


IPW



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q79007

Koichi KAWAMURA, et al.

Appln. No.: 10/735,769

Group Art Unit: 1756

Confirmation No.: 3973

Examiner: Daborah Chacko Davis

Filed: December 16, 2003

For: PATTERN FORMING METHOD AND SUBSTANCE ADHERENCE PATTERN MATERIAL

RESPONSE UNDER 37 C.F.R. § 1.111

MAIL STOP AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated October 11, 2005, please consider the remarks as submitted herewith on the accompanying pages.

REMARKS

Claims 1-23 are all the claims pending in the application.

I. IDS Form

Applicants note that the Examiner did not initial the citation of Younan Xia, et al., "Soft Lithography" in the Non Patent Literature Documents section of the PTO/SB/08 Form submitted with the Information Disclosure Statement filed on June 30, 2005. Applicants respectfully request the Examiner to initial this reference and return a copy of the initialed PTO/SB/08 Form with the next action. A courtesy copy of the PO/SB/08 Form is submitted herewith for the Examiner's convenience.